[Claims]

1. A decomposition inhibitor used for inhibiting the decomposition of hydrogen peroxide contained in an etching liquid composition for titanium nitride, comprising azole compounds as an active component.

2. The decomposition inhibitor according to claim 1, further comprising water.

3. The decomposition inhibitor according to claim 1 or 2, further comprising a water-soluble organic solvent.

4. The decomposition inhibitor according to any one of claims 1 to 3, comprising at least one compound selected from 1,2,4-triazole, 1,2,3-triazole, imidazole and benzimidazole as the azole compound.

5. The decomposition inhibitor according to any one of claims 1 to 4, which is for adding azole compounds to an etching liquid composition at a ratio of 2 mmol/L or more relative to 100 ppm of titanium nitride in the etching liquid composition.

6. A method for inhibiting the decomposition of hydrogen peroxide contained in an etching liquid composition for titanium nitride, which uses the decomposition inhibitor according to any one of claims 1 to 5.